

20th Anniversary of KSDT
KISM 2022
Korean International Semiconductor Conference on Manufacturing Technology 2022
November 13-16, 2022 | Paradise Hotel Busan (Haeundae Beach), Busan, Korea

Session Title:	[MA1] Nanoscale Thin Film Deposition I
Session Date:	November 14 (Mon.), 2022
Session Time:	13:00-14:30
Session Room:	Room A (Capri Room, 2F)
Session Chair:	Prof. Bonggeun Shong (Hongik Univ., Korea)

[MA1-1] [Invited] 13:00-13:30

Thin Film Process Engineering for Continued Memory Device Scaling
Dongwon Choi (SK hynix, Korea)

[MA1-2] 13:30-13:50

Atomic Layer Deposition of Pt Thin Films Using Dimethyl (N,N-Dimethyl-3-Butene-1-Amine-N) Precursor
Ji-Hu Baek and Se-Hun Kwon (Pusan Nat'l Univ., Korea)

[MA1-3] 13:50-14:10

Atomic Layer Deposition of Ru for Emerging Ru Interconnects
Yohei Kotsugi (TANAKA Precious Metals, Japan), Youn-Hye Kim, Taehoon Cheon (Yeungnam Univ., Korea), and Soo-Hyun Kim (Yeungnam Univ., Korea)

[MA1-4] 14:10-14:30

Low Temperature Thin Film Deposition Using Single-Wafer Thermal RPCVD with Extreme Heat Control
Dooyeol Ryu, Wooduck Jung, Donggyu Yim, Seungwoo Shin, and Dooyeol Ryu (Eugene Tech. Co., Ltd., Korea)